



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : HIGH ENERGY LASER LINE COATING
 $R_s, R_p > 99\% @ 1064 \text{ nm}, 0^\circ - 45^\circ \text{ AOI}$
3. CLEAR APERTURE (S1, S2) : $> 90\%$ (CA)
4. SURFACE QUALITY (S1, S2) : 20/10 (S/D)
5. SURFACE FLATNESS (S1, S2) : $\lambda/6 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) : $< 3 \text{ arcmin}$
7. CHAMFER: $< 0.2 \text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : POLISH

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|--|--------|--------------|--|--------|-------|-----|
| DRAWING PROJECTION | | | LBTEK | | | |
| | NAME | DATE | LPM12-1064P-HP | | | |
| DRAWN | YZENG | Apr./25th/24 | HIGH ENERGY LASER LINE MIRROR $\text{Ø} 30 \text{ mm} \times 6 \text{ mm}, 1064 \text{ nm}$ | | | |
| APPROVAL | WCHENG | Apr./25th/24 | MATERIAL | WEIGHT | SCALE | REV |
| FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES | | | UVFS | 9.34 g | 2:1 | A |